

1 9. (Three Times Amended) A method of removing at least one particle from a
2 [portion] surface of a metal [layer on] plug disposed over a substrate comprising:
3 depositing a slurry onto a metal layer over the metal plug [the substrate];
4 polishing the metal layer [and the substrate]; and
5 after polishing the metal layer, rinsing [a] the surface of the metal plug with a
6 solution comprising hydrogen peroxide.

1 18. (Three Times Amended) A method comprising:
2 polishing [the] a metal layer over a conductive plug with a slurry; [and]
3 after polishing the metal layer, introducing a rinsing solution onto [a] the [metal]
4 conductive plug, the rinsing solution [comprising] comprises hydrogen peroxide.